The Laurell *HL* Advantage

Choosing your best spin processor

All Laurell Technologies HL series spin processors come with the following benefits

Windows® Wireless Touchscreen Controller: Class 3 Bluetooth® allows cable-free programming and control

Laurell Touch Interface: Program creation and operation information on one screen

Time: 1 second to 99 minutes 59.9 seconds in 0.1 second increments

Programs: Twenty 51-step programs or manual mode — number of steps/programs can be user reconfigured through SPIN 3000

SPIN 3000: Field-proven advanced PC interface software, not required to program system

Fluid-control lid: Directs materials towards rear drain to prevent drips when opening the process chamber

Chemically-resistant lid: With Ø3/4" (Ø19 mm) center opening

Ø1.5" (Ø38 mm) NPP Drain Port and Gas purge

Safety door interlock: Disallows rotation when door is open

Safety door latch: Requires deliberate action to open process chamber

Safety door lock: Prevents chamber opening while program is running, or during chuck rotation after program ends

Vacuum interlock: Disallows rotation when there is insufficient vacuum

Corrosion-proof configuration: No exposed metal — therefore, no degradation using strong acids or bases

Glovebox-ready configuration: Continuous seal purge with CDA or inert gas required

Lifetime Process Support

Choose a size that fits your substrate

	23 Series	8 Series	15 Series
Round substrates up to:	150 mm/ 6 inches	200 mm/ 8 inches	300 mm/ 12 inches
Square substrates up to:	125mm/ 5 inches	178 mm/ 7 inches	230 mm/ 9 inches

Measurements given are the largest suggested diameter or length of a side

Ø150mm Ø200mm Ø300mm
⊠125 mm ⊠178 mm ⊠230 mm
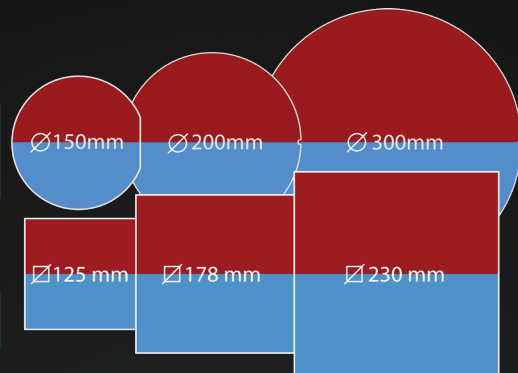
H6M23N   *H6M8N*   *H6H15N*

Required facilities

95 - 250 V AC at 47-63 Hz

60-70 psig (4-5 bar) of N_2 or Clean Dry Air

20-28 inches (~504-711mm) Hg. 1.7 - 4.5 SCFM (0.127 M^3/min.)

Choose the housing material based on your process and chemistry:

Polypropylene Copolymer

- An exclusive copolymer resistant to solvents, strong acids, and bases

Teflon®

- Widest chemical resistance available
- Required for processing aggressive chemistries such as "Piranha" etch and certain acids at high concentrations

Choose the motor performance that suits your process, now and in the future:

Mz Standard Performance Motor

- Brushed motor suitable for N_2 or Ar environments
- Speed range from 100 to 12,000 RPM
- Acceleration up to 13,000 rpm/second*

Substrate size / weight dependent

Hz High Performance Motor

- Brushless motor
- Speed range from 1 to 12,000 RPM
- Acceleration up to 30,000 rpm/second*
- No measurable speed error
- Power to spin larger, heavier substrates
- Forward/Reverse rotation
- Programmable Agitation
- Limited lifetime warranty

Choose the accessories that will help you achieve your best results:

Dispense Solutions

- **UD-3** center dispense
- **UD-3b** off-center dispense and Edge Bead Removal
- **Single Shot Dispense** from an open container
- **Single syringe** manual dispense
- **Multi-syringe** manual dispense

Chucks: Standard and Custom

- **Non-vacuum** chucks
- **Minimum contact** chucks
- **Fragment** chucks
- **Basket processing** chucks
- **CD/DVD** chucks
- **High-Porosity** chucks
- **Lens** chucks
- **Embedded** chucks

Wireless Control

- **Remote vacuum** switch
- **Foot switch** multifunction for hands-free control
- **Multi-System** control

Choose the experts:

Since 1985 **Laurell Technologies** has created a broad range of unique solutions for our customers

Laurell EDC systems for aqueous processing are custom designed to fit your specific chemistry & process requirements, and to ensure your safety

Discuss your needs with our experienced engineers for a complete solution

CE **RoHS**

ETL c US **Intertek**

All Laurell products that carry the ETL mark meet, or exceed, specific US and Canadian product safety standards